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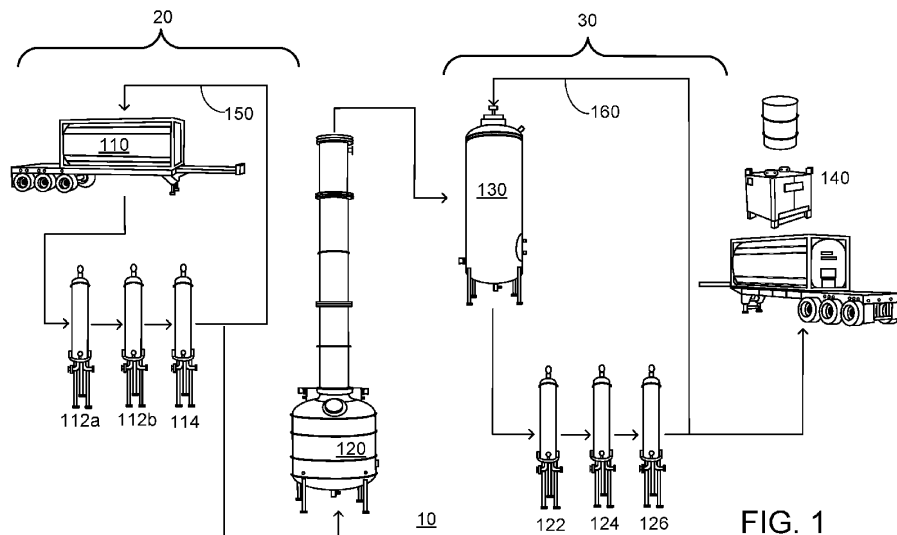
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(54) Title: SYSTEMS AND METHODS FOR PURIFYING SOLVENTS



(57) Abstract: The present disclosure is directed to methods and systems of purifying solvents. The purified solvents can be used for cleaning a semiconductor substrate in a multistep semiconductor manufacturing process.